

**Marked-Up Copy**

Serial No: NEW CONT APP.

Amendment Filed on:

HEREWITH 7-15-03

IN THE SPECIFICATION

Page 32, lines 5-16, please delete the paragraph and replace it with the following paragraph:

With the fourth [exposure apparatus] light source unit according to the present invention, the temperature dependence data may further include data on temperature dependence of the center wavelength of the laser beam oscillated from the laser light source, and the first control unit may perform wavelength control of the laser light source together, when performing the absolute wavelength calibration. In such a case, the absolute wavelength calibration can be completed within a shorter period of time compared with the case when wavelength control of the laser beam is not performed. However, the wavelength of the laser beam does not necessarily have to be controlled, when performing the absolute wavelength calibration.

Page 138, line 18, through page 139, line 6, please delete the paragraph and replace it with the following paragraph:

Meanwhile, instead of driving the driving elements 74a, 74b, and 74c to correct the environmental change including the atmospheric change of the projection optical system PL referred to above by providing instructions to the image forming characteristics correction controller [44] 78, the main controller 50 may obtain the change in pressure, temperature, and humidity from the standard state based on the measurement values of the environmental

sensor 77 at every predetermined timing since exposure on the first wafer has started, and calculate the amount of wavelength change to almost cancel out the environmental change of the image forming characteristics of the projection optical system PL due to the change in pressure, temperature, and humidity. And, according to the amount of wavelength change calculated, the main controller 50 may positively change the oscillation wavelength of the laser light source 160A. The environmental sensor 77 may be a sensor to detect the atmosphere.

Page 161, line 24, through page 162, line 20, please delete the paragraph and replace it with the following paragraph:

The exposure apparatus in the embodiment above is made by assembling various subsystems including elements defined in the claims of the present application so as to keep a predetermined mechanical precision, electrical precision, and optical precision. In order to ensure these areas of precision, prior to and after the assembly, adjustment (for example, optical axis adjustment) is performed on various optical systems such as the illumination optical system 12 and the projection optical system PL to attain a predetermined optical precision, adjustment is performed on various mechanical systems to attain a predetermined mechanical precision, and adjustment is performed on various electrical systems to attain a predetermined electrical precision, respectively. Of these adjustments, since the light source for adjustment (testing) does not require high power when the properties of various optical systems are adjusted, with the light source 16 previously described, the arrangement can be simplified so as to use one or several fiber amplifiers [167] 168 as the light source. In such a case, light having almost the same wavelength as the wavelength of the exposure light can be easily generated, and can be used for adjustment. Therefore, an accurate adjustment can be made with a cost effective light source having a simple arrangement. In the case of